

ULTRARAM™: Progress and prospects

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Outline

- Introduction to **ULTRARAM™**
- Progress and challenges (scaling, arrays)
- Prospects

Introduction to ULTRARAM™

ULTRARAM™ concept

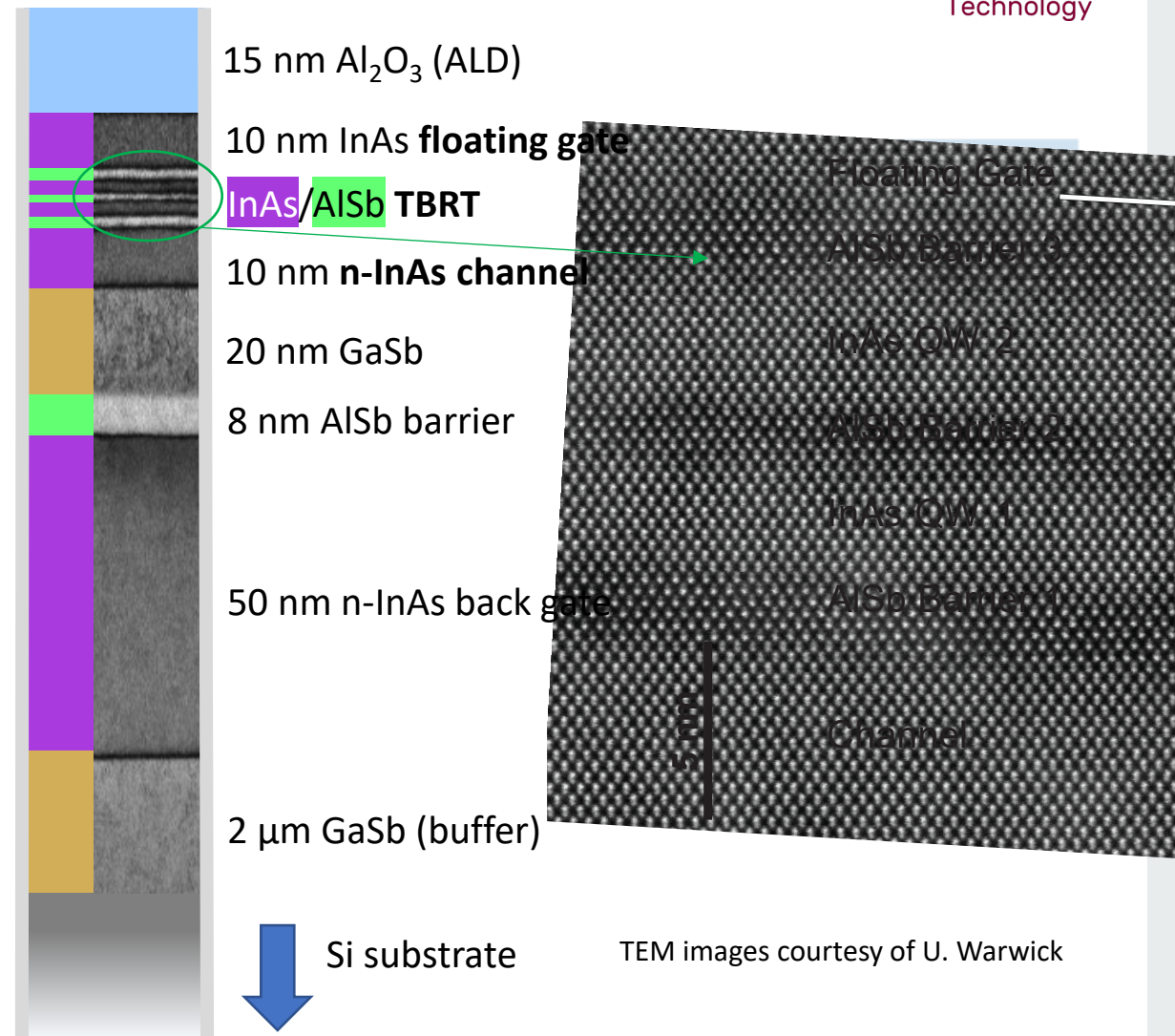
US10243086B2, US11929120B2 + pending

- Floating gate memory (like flash)
- Compound semiconductor based
- High-mobility InAs channel
- Grown on silicon substrates
- Oxide tunnelling barrier is replaced by a

Triple barrier resonant tunnelling structure (TBRT)



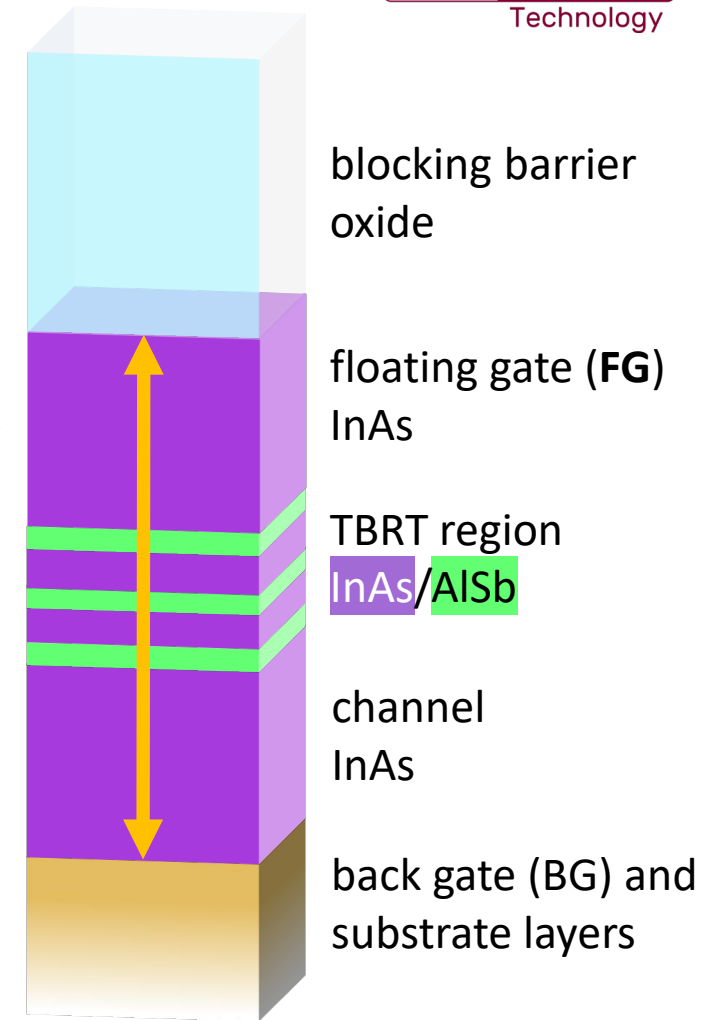
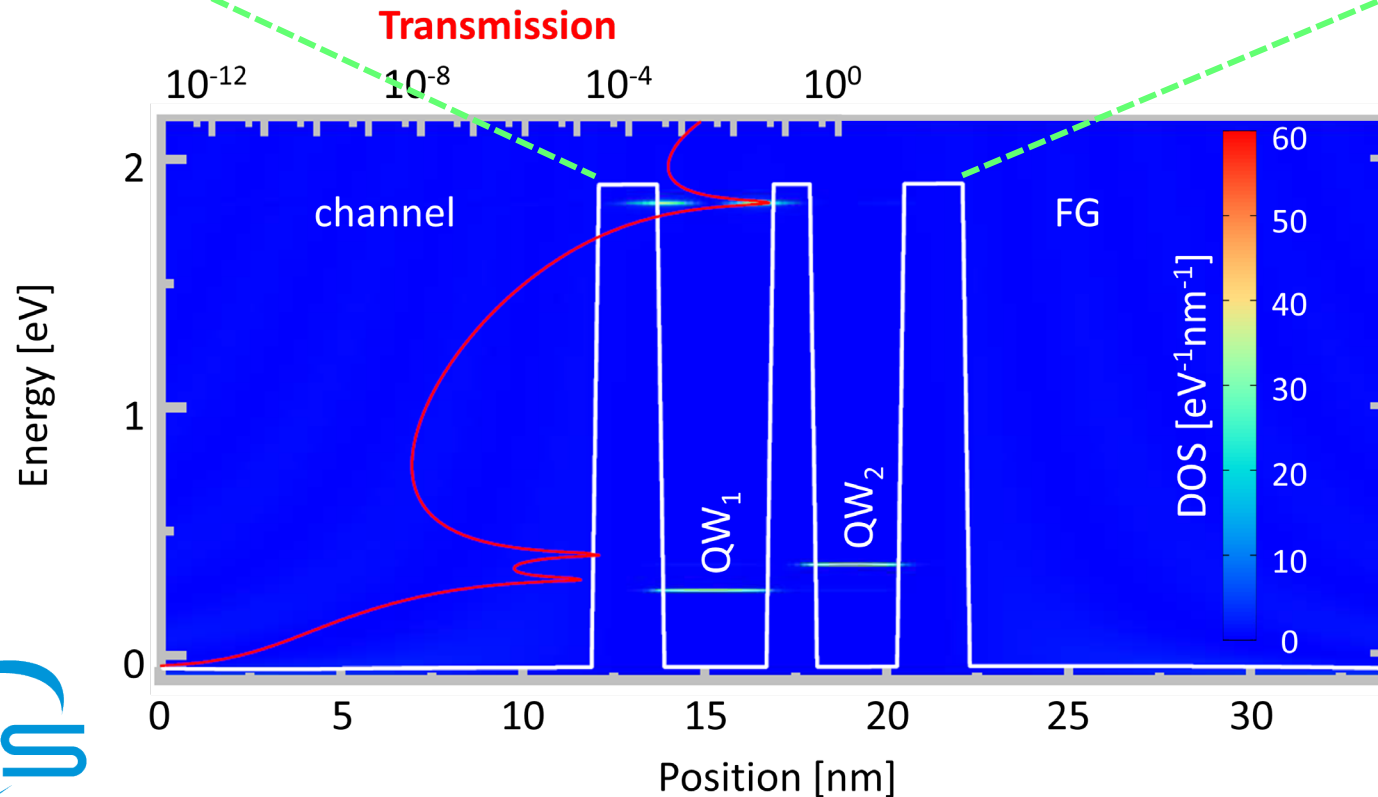
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ULTRARAM™ cell

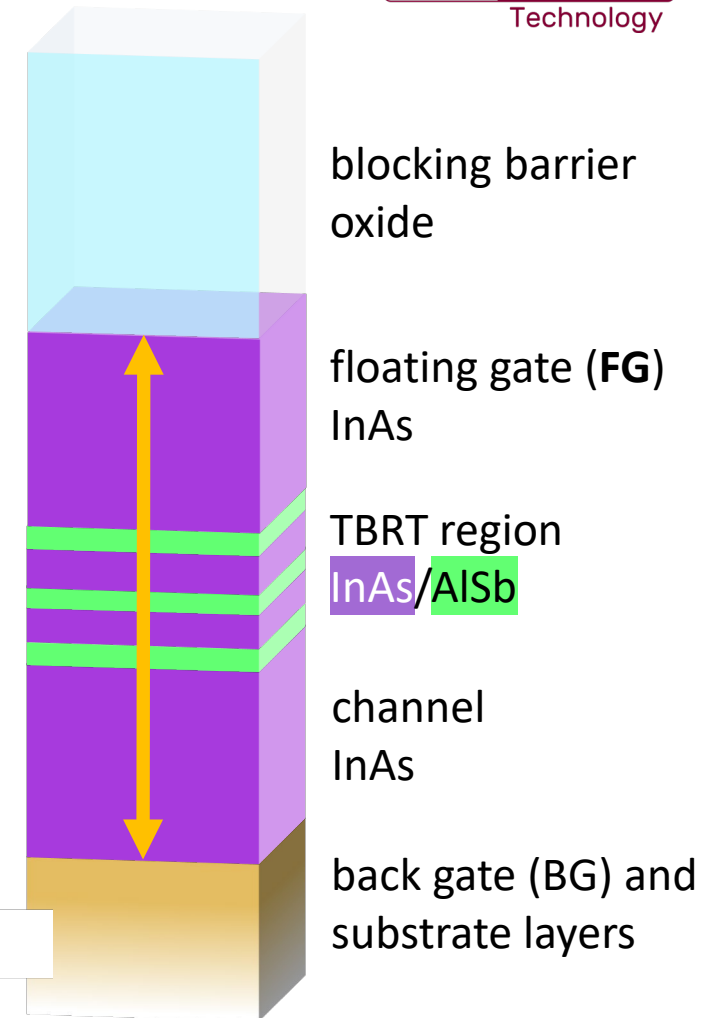
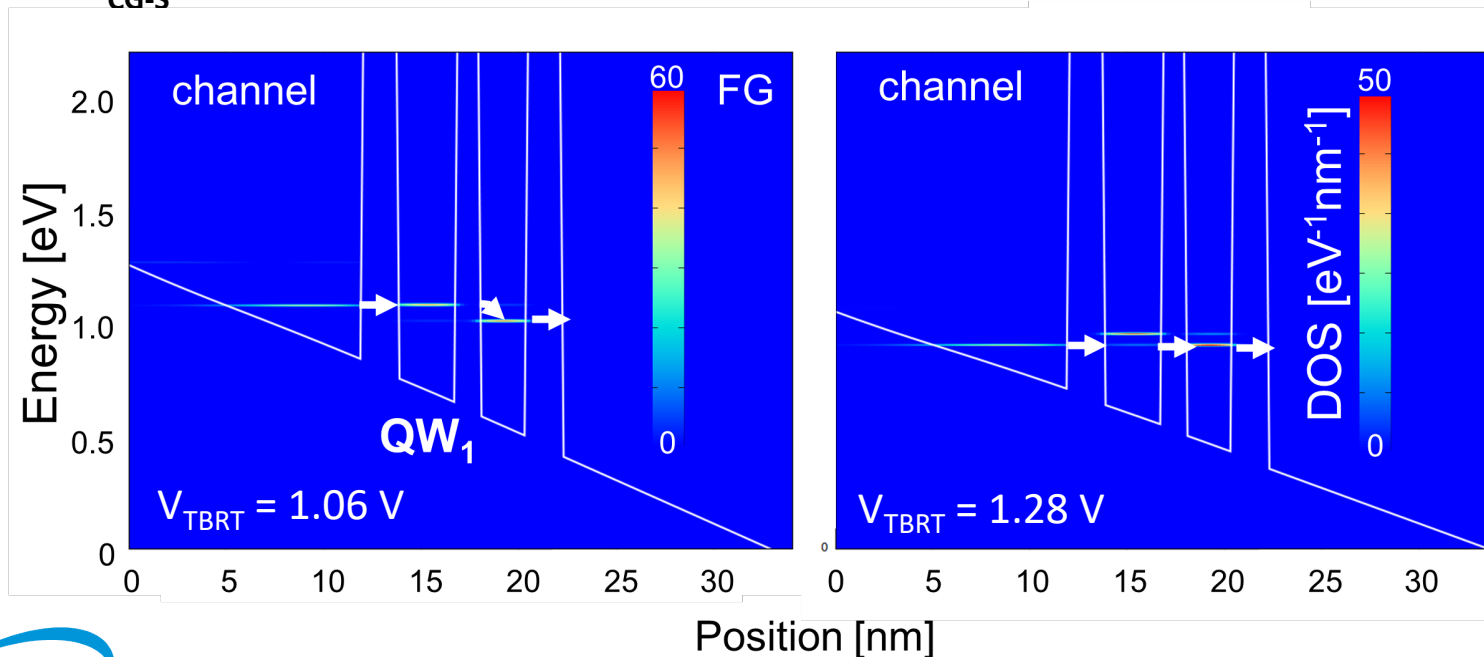
Charge retention (no bias)

1.8 nm AlSb / 3.0 nm InAs / 1.2 nm AlSb / 2.4 nm InAs / 1.8 nm AlSb



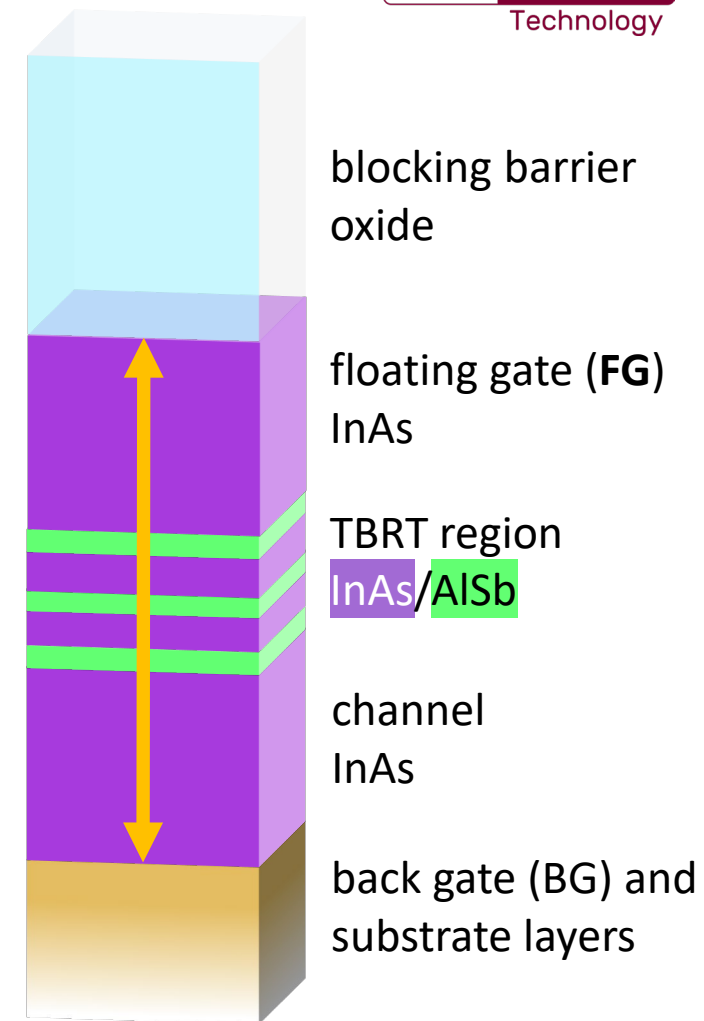
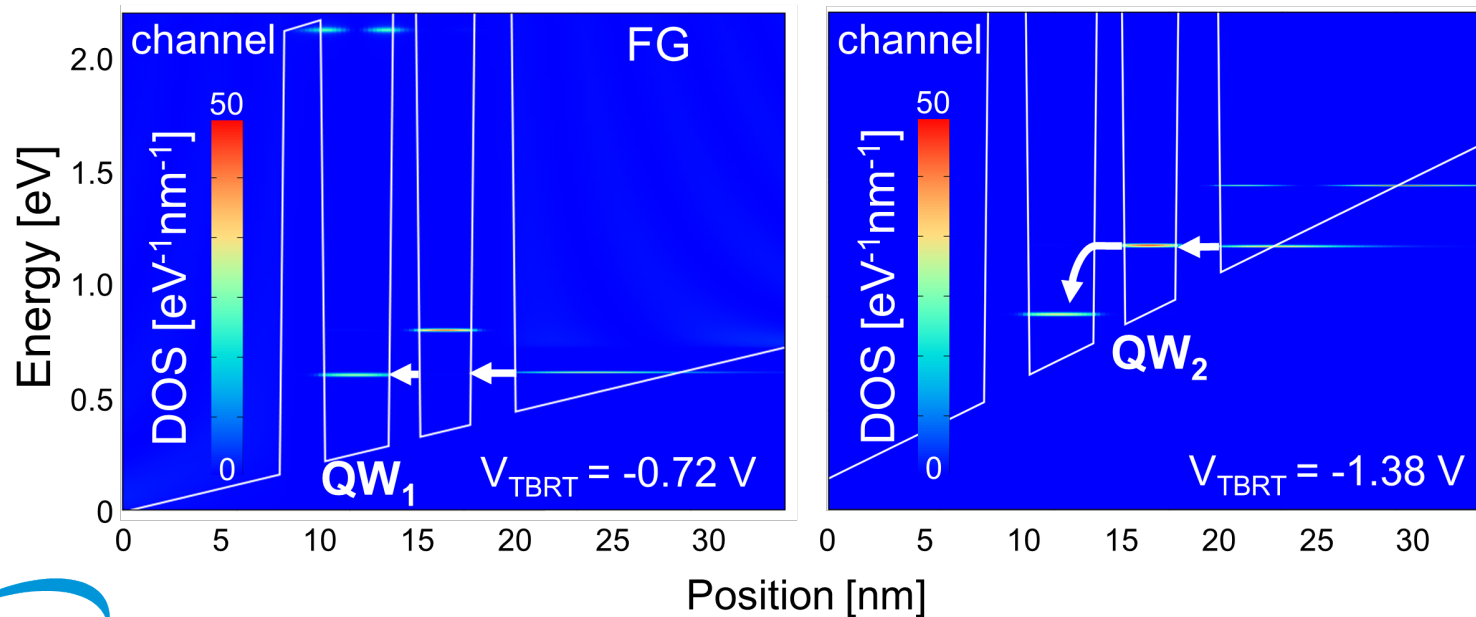
Program and erase (≤ 2.5 V)

Program (P) cycle: add electrons to the floating gate
 $V_{CG-S} < +2.5$ V

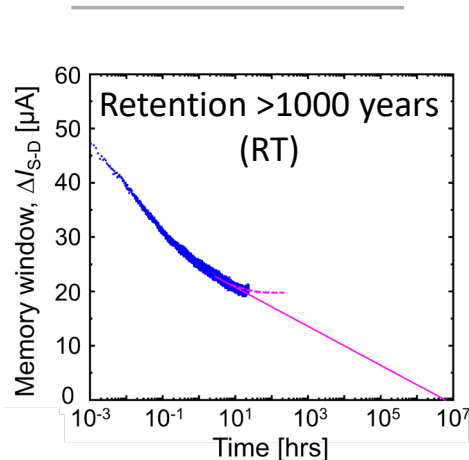


Program and erase (≤ 2.5 V)

Erase (E) cycle: remove electrons from the floating gate
 $V_{CG-S} < -2.5$ V

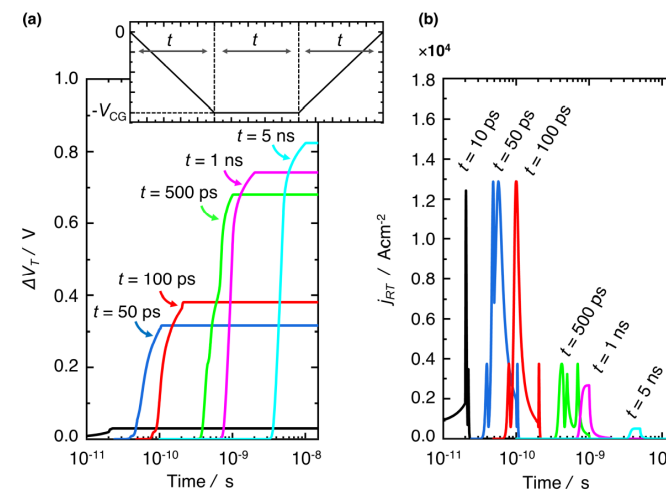
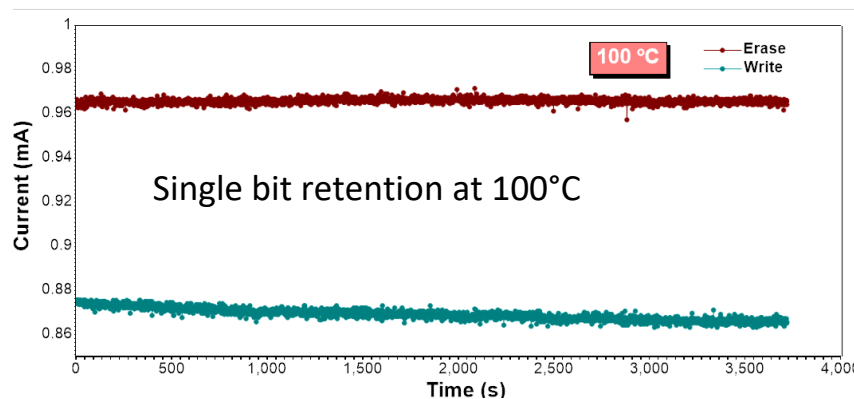


Key ULTRARAM™ features



- Charge-based memory, like DRAM, flash, SRAM (99% of market)
- Lowest switching energy ($\frac{1}{2}CV^2$: low capacitance, low voltage)
- Very robust charge storage (unaffected by material defects, TBRT variations, temperature, light...)
- Intrinsically fast (resonant tunnelling)

Hodgson *et al.*, Adv. Electron. Mater. 2101103 (2022)



Lane, PhD Thesis, Lancaster University (2021)

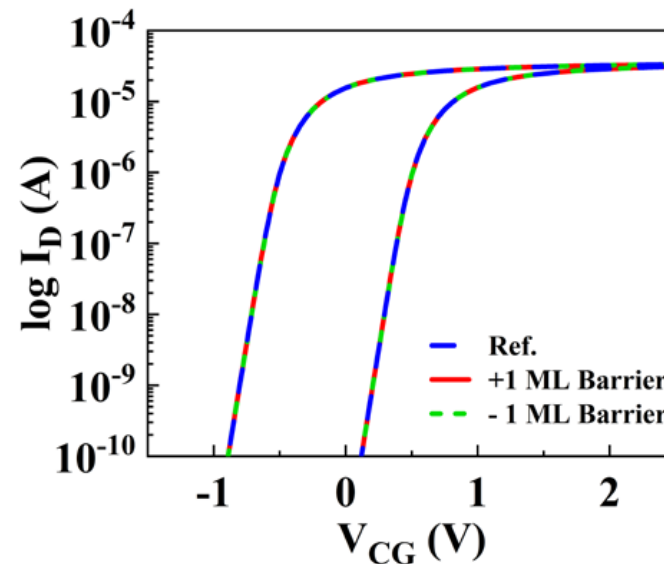
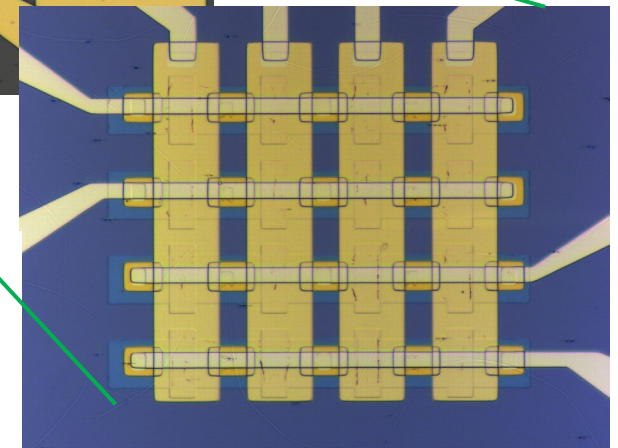
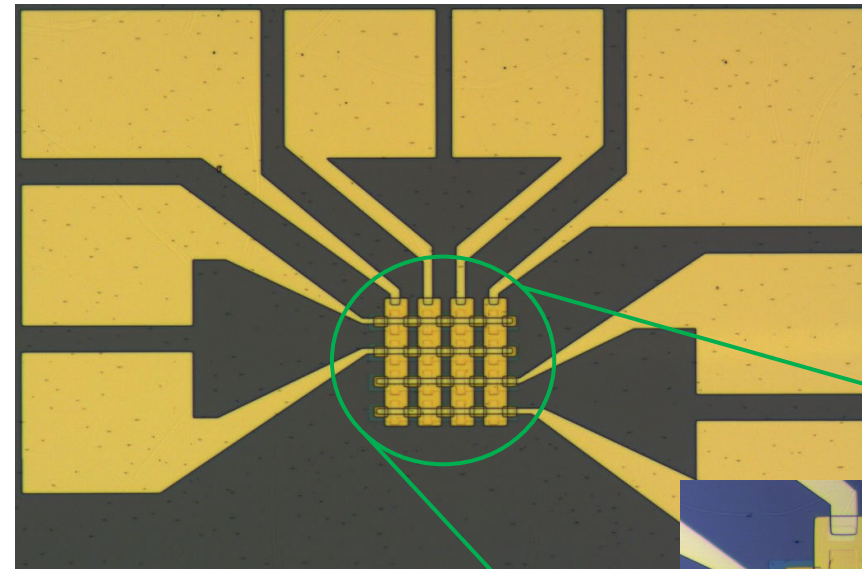


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Progress and challenges

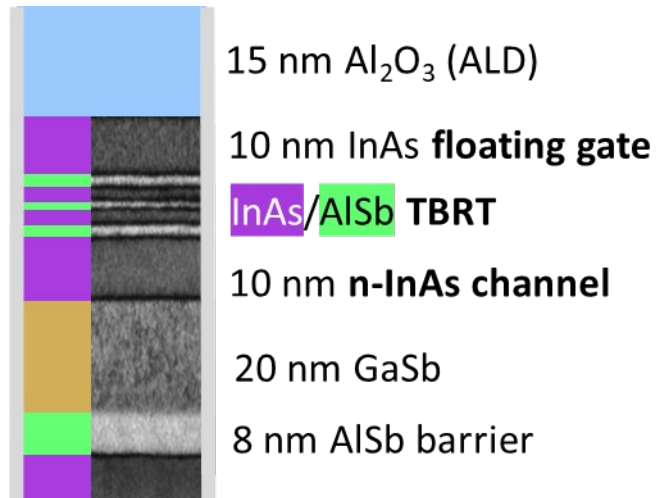
ULTRARAM™ arrays

- Under active development
 - 4/16, 16/64 bare arrays
 - FEI logic for decoding (pat. pending)
 - Then 256, 256², 256² x 16, etc. decoded arrays
- Architecture (NOR-like) well understood
- Main challenge is 0/1 contrast ratio, which is \ll than the 10^5 predicted



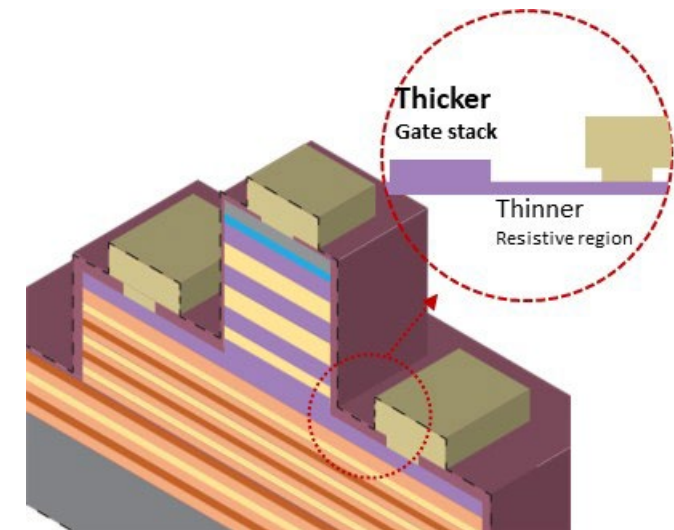
Kumar *et al.*, submitted IEDM (2024)

ULTRARAM™ scaling



Dry etching to the <10 nm InAs channel is challenging, and over-etching is inevitable

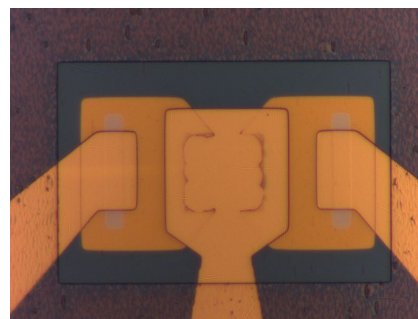
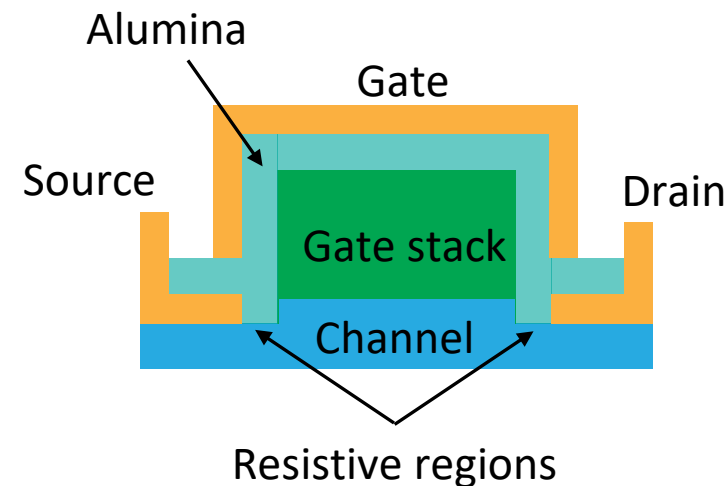
This creates a large parasitic resistance that dampens 0/1 readout contrast



ULTRARAM™ scaling

The solution is to minimise the distance between channel contacts and the gate stack by insulating with a thin layer

An overlapping gate contact can further enhance conductivity in this small region, for the target device only



Device fabrication using this patent-pending process is underway

Prospects

Beachhead ULTRARAM™ markets

While the ambition is to compete with DRAM, we are identifying applications that take advantage of ULTRARAM™'s remarkable properties

- Ultralow energy consumption
- Very robust data storage
- Operation at high and/or the lowest temperature



We are also developing In-ULTRARAM™ computing for analogue MAC operations in AI

